

HDP-CVD DEPOSITION PROCESS FOR FILLING HIGH ASPECT RATIO GAPS

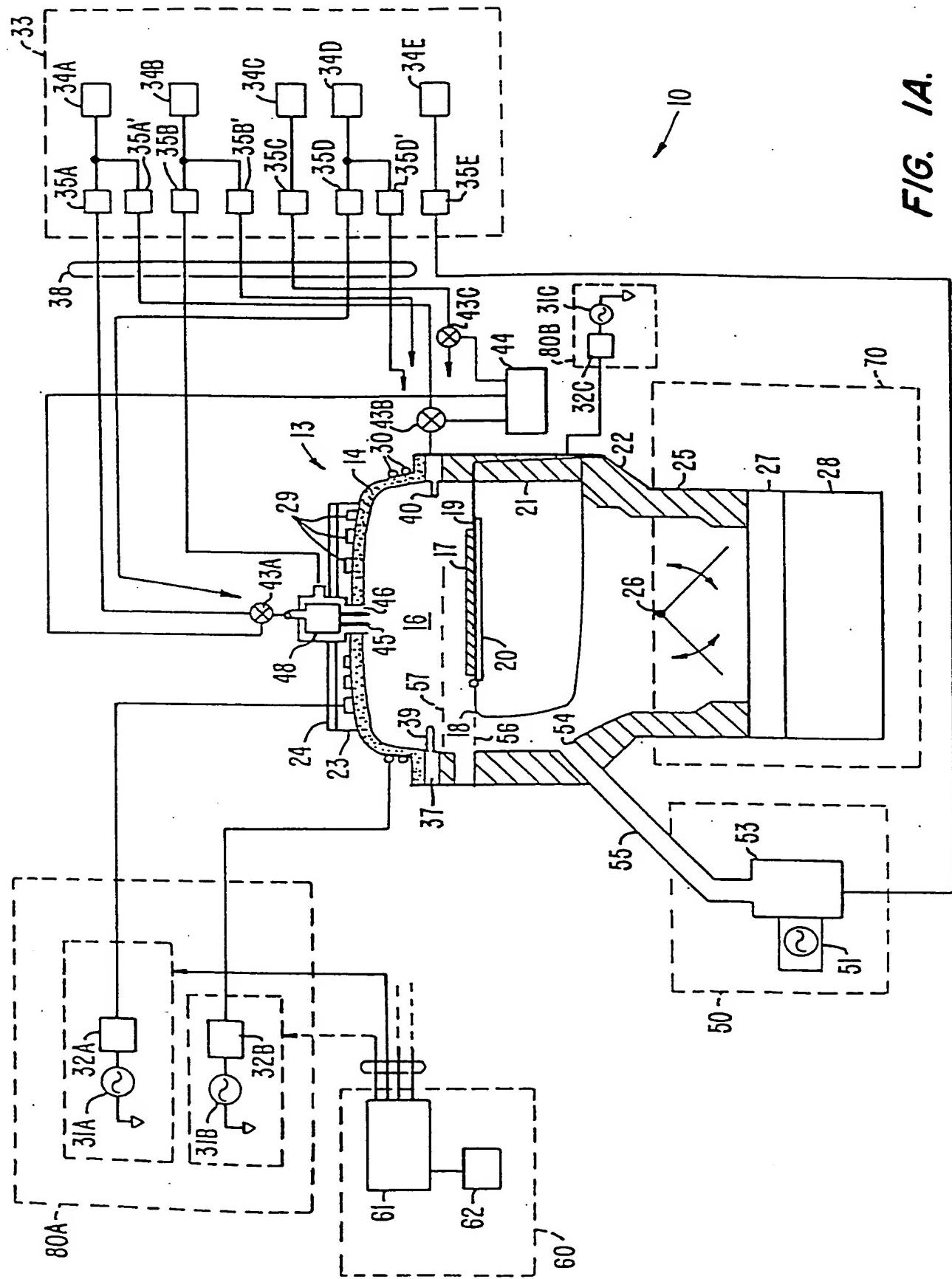
Inventors: Zhengquan Tan et al.

US Patent Application No. Unassigned; Filed: Herewith

William L. Shaffer (650-326-2400)

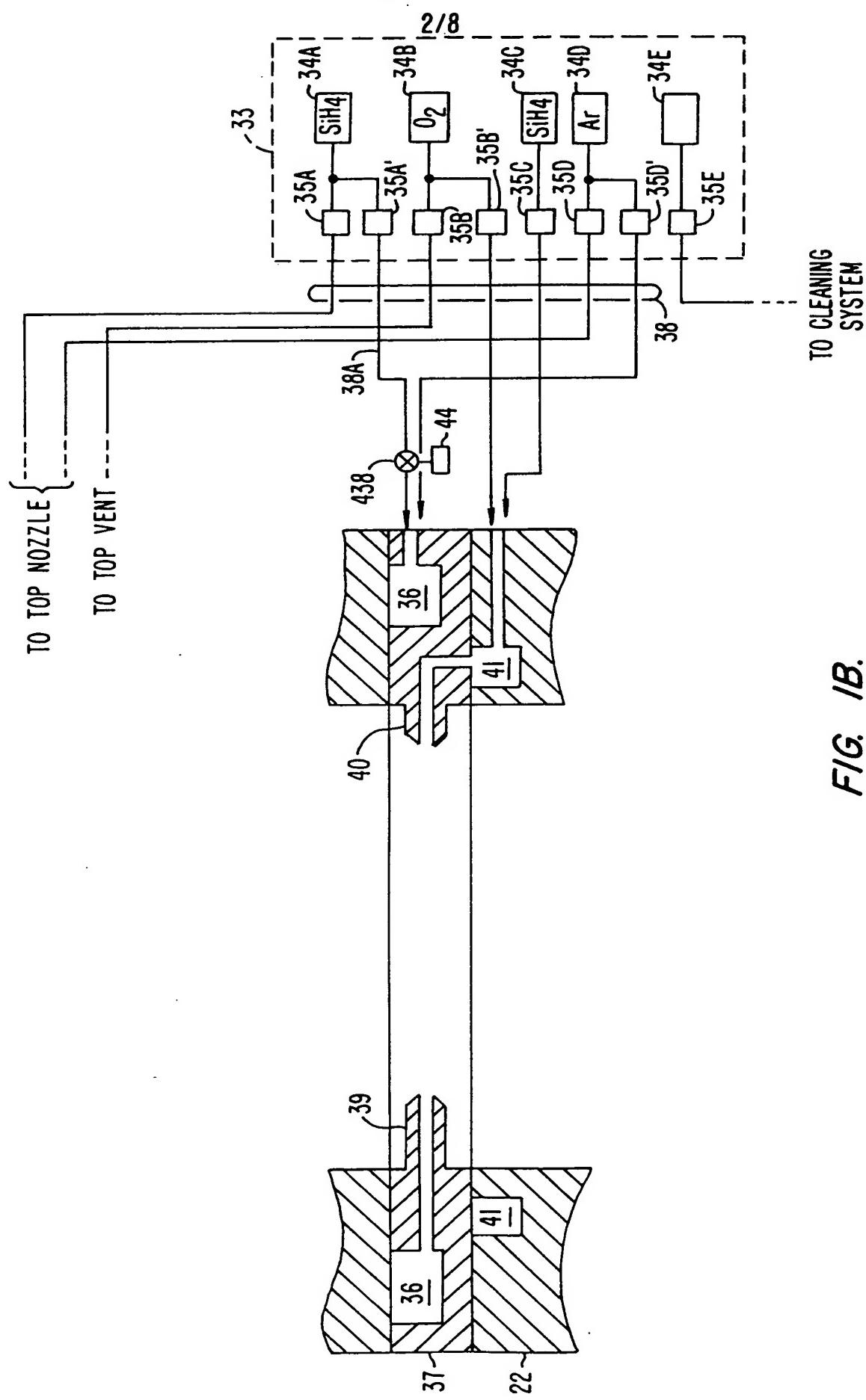
Attorney Docket No.: A5771C1/T42210

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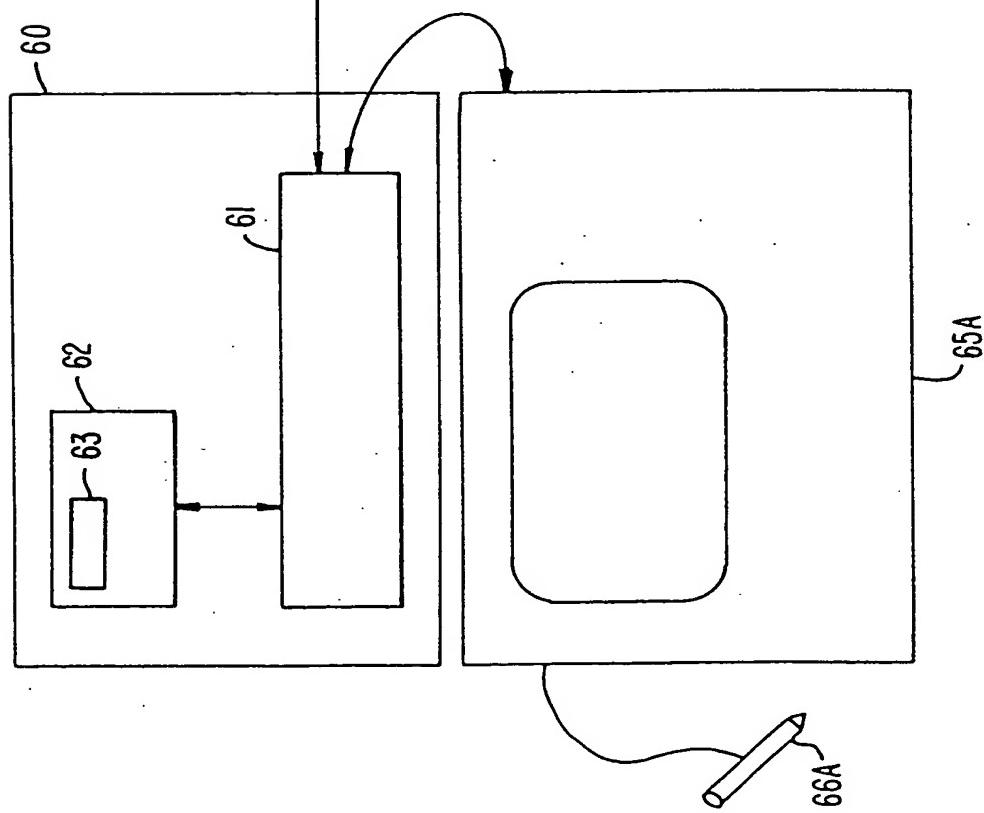
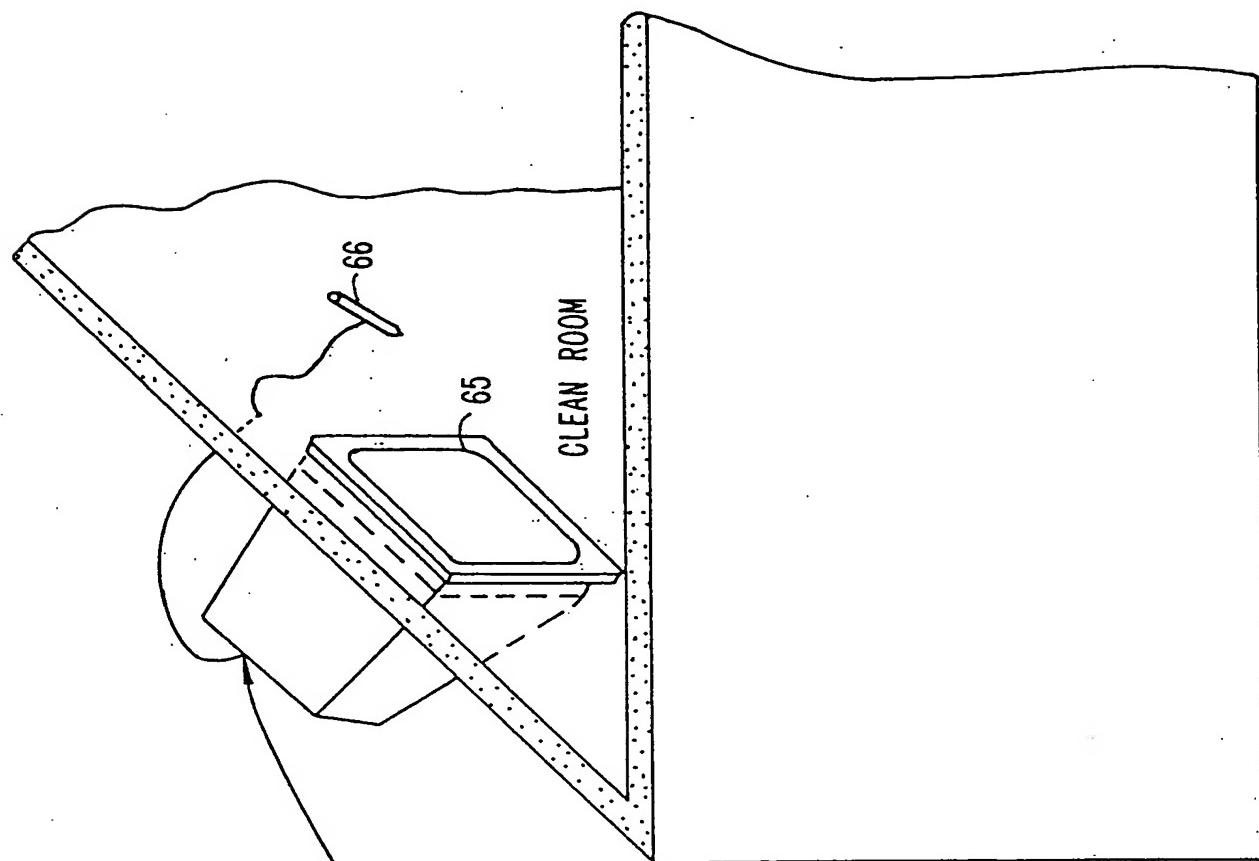


FIG. 1C.

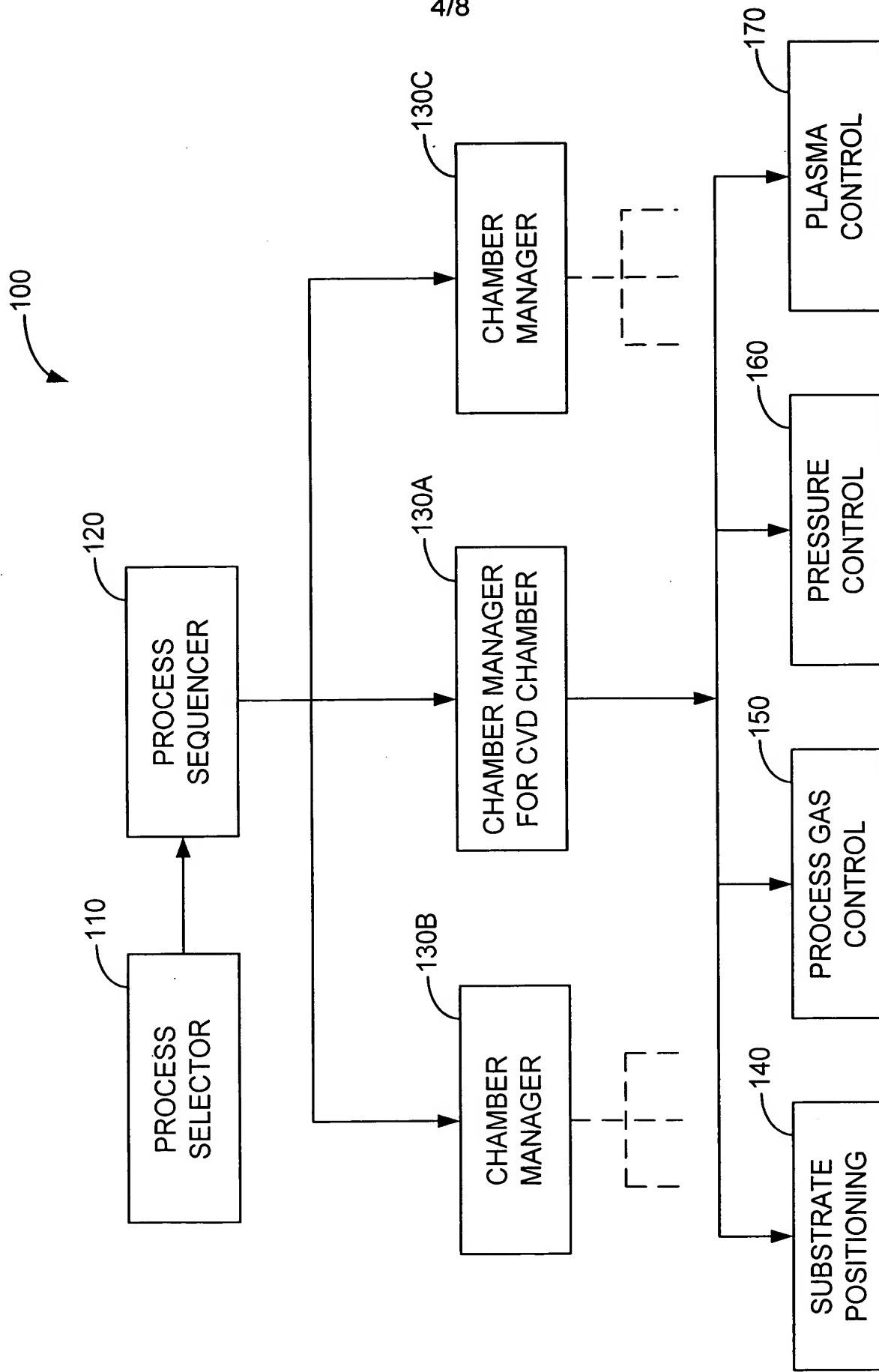


FIG. 1D.

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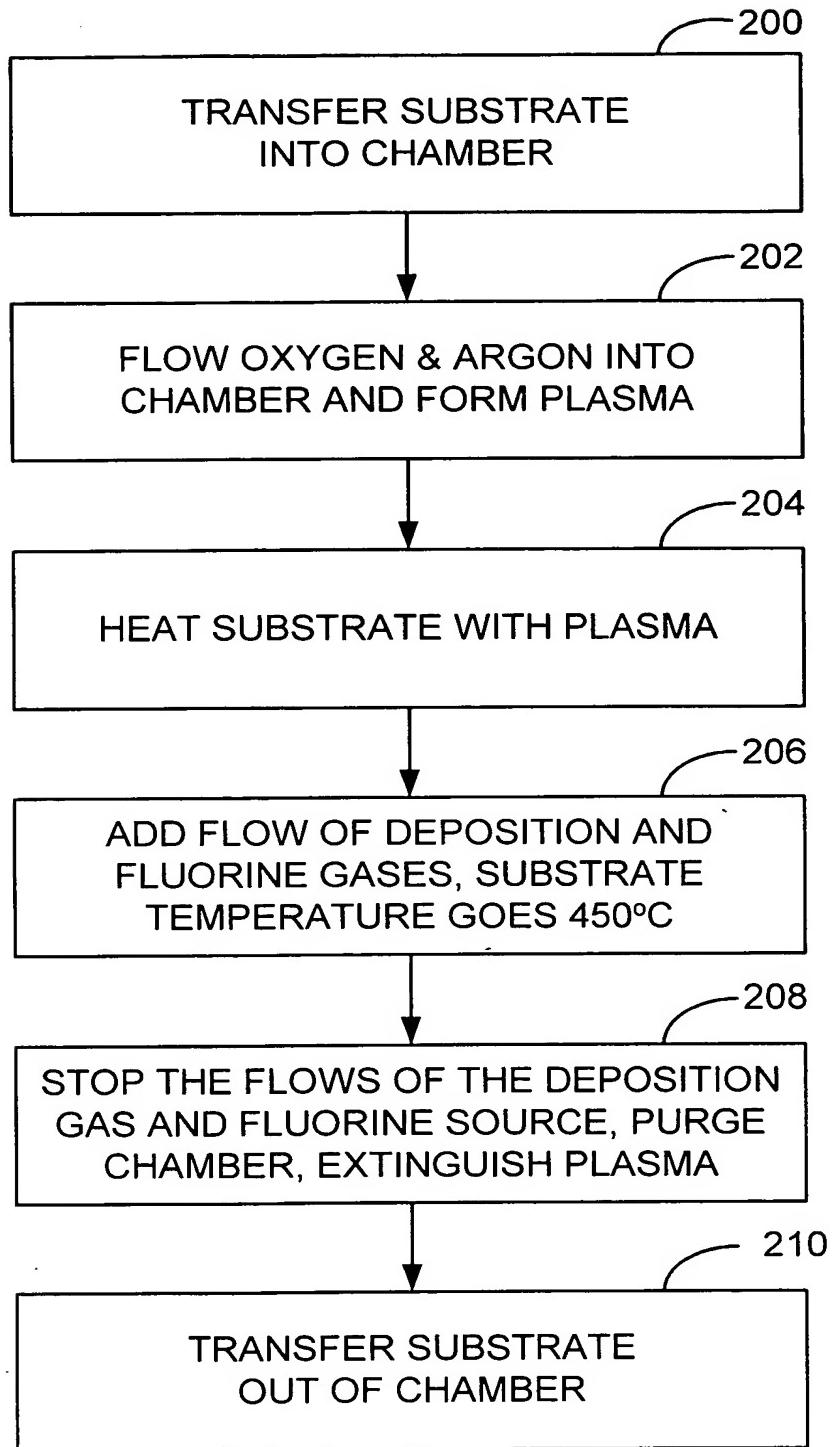


FIG. 2.

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FIG. 3A.

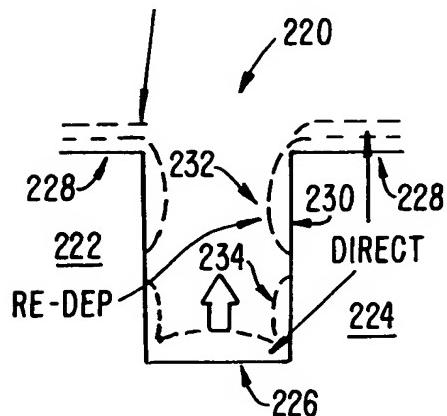


FIG. 3B.

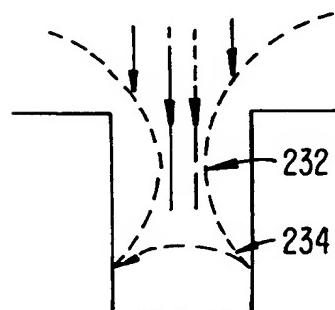
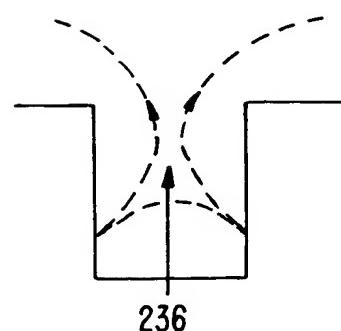


FIG. 3C.



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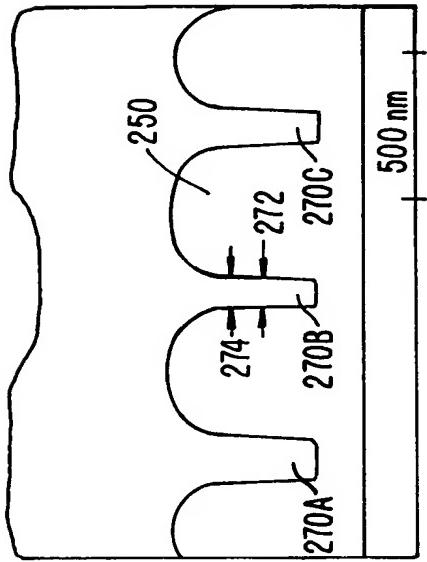


FIG. 5A.

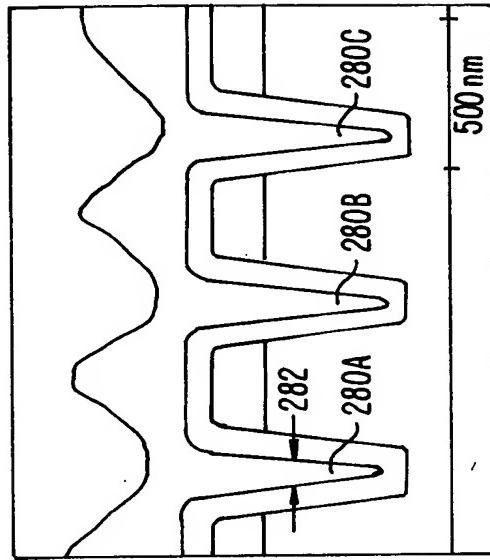


FIG. 5B.

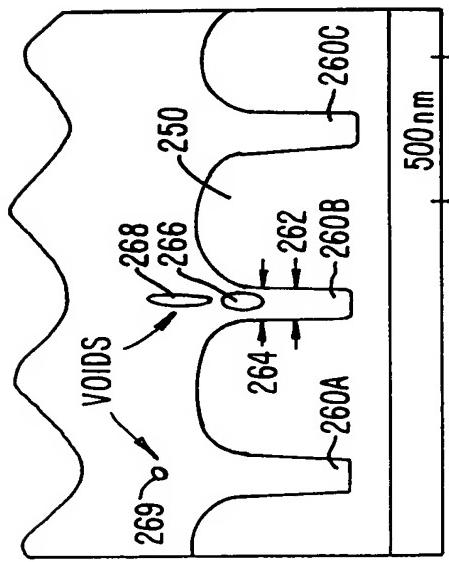


FIG. 4A.

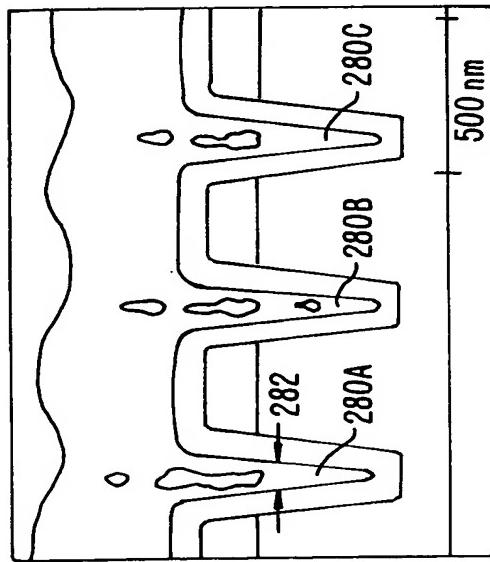


FIG. 4B.

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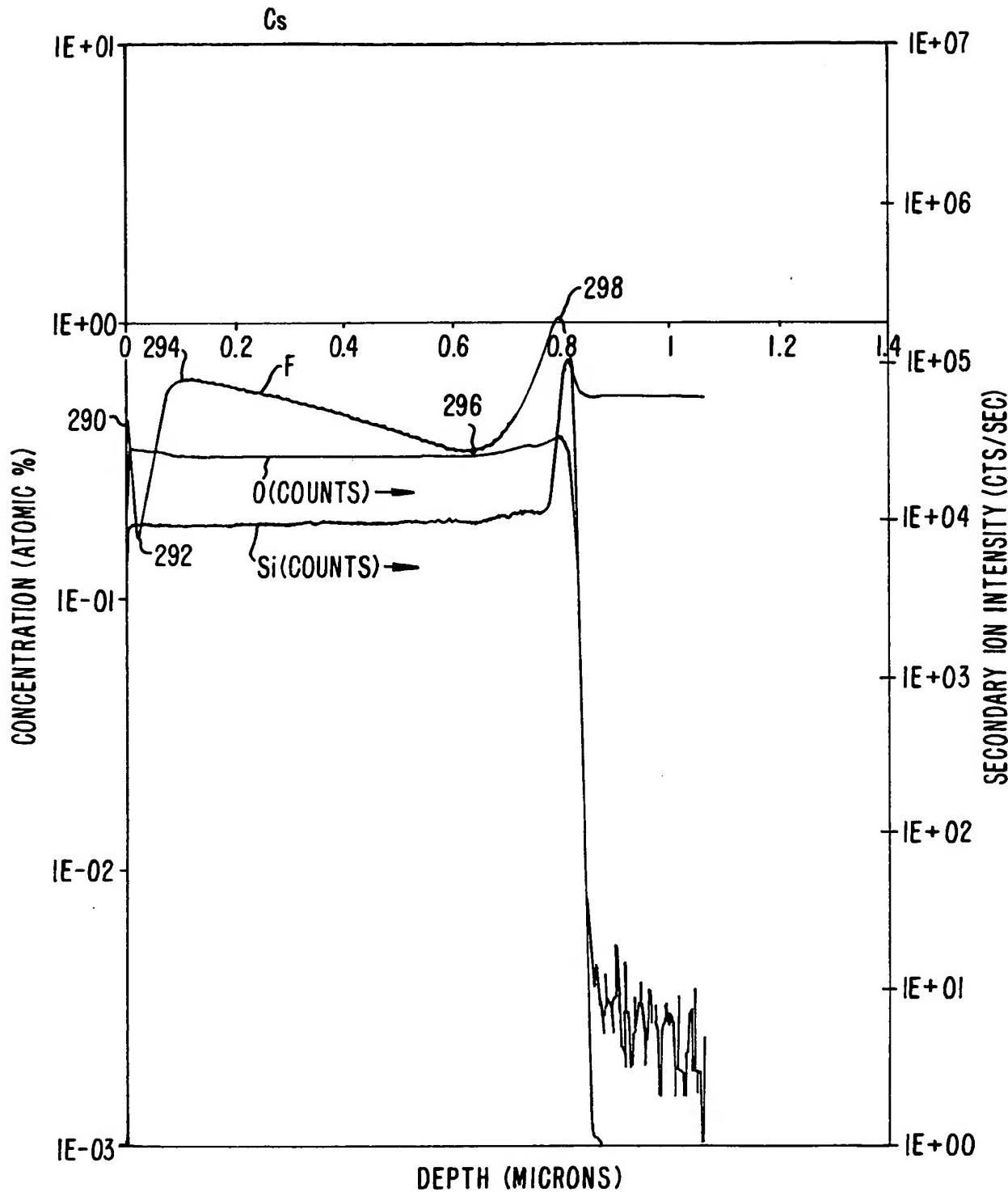


FIG. 6.